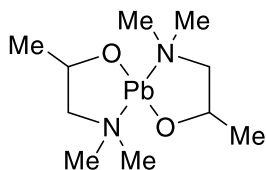


Catalog # 82-2155 Bis(1-dimethylamino-2-methyl-2-propanolate)lead(II), 98% Pb(DMAMP)2



## Thermal Behavior:

- Melting point: 65°C [1]
- Vapor Pressure: 1.97 Torr at 126°C
- TGA diagram and data is available in [1]

## Technical Notes:

1. ALD/CVD precursor for lead thin film deposition

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
Pb(Zr,Ti)O <sub>3</sub>	CVD	Ethylcyclohexane solution injection	5 Torr	Zr(MMP) <sub>4</sub> , O <sub>2</sub> , Ti(MMP) <sub>4</sub>	400°C	1
PbO	ALD	126°C	0.5-0.8 Torr	H <sub>2</sub> O	200°C	2
PbTiO <sub>3</sub>	ALD	116°C	0.8-1.5 Torr	Ti(O <sup>t</sup> Bu) <sub>4</sub> ; H <sub>2</sub> O	200°C	3
	ALD	90°C	0.9 Torr	Ti(O <sup>t</sup> Bu) <sub>4</sub> ; H <sub>2</sub> O; O <sub>3</sub>	200°C	4
	ALD	90°C	1.6 Torr	Ti(NMe <sub>2</sub> ) <sub>4</sub> ; O <sub>3</sub>	250°C	5

## References:

1. [Integr. Ferroelectr. 2006, 81, 261](#)
2. [Electrochem. Solid-State Lett. 2007, 10, G89](#)
3. [J. Electrochem. Soc. 2007, 154, G69](#)
4. [ECS Trans. 2009, 19, 829](#)
5. [J. Vac. Sci. Technol. A. 2019, 37, 020917](#)